Supporting Information for:

Synthesis and Characterization of MO\{OSi(O'Bu)\}_3 and MO_2\{OSi(O'Bu)\}_2 (M = Mo, W): Models for Isolated Oxo-Molybdenum and -Tungsten Sites on Silica and Precursors to Molybdena- and Tungsta-Silica Materials

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Figure 1. TGA trace for I under a flow of nitrogen with a heating rate of 10 °C min⁻¹.
Figure 2. TGA trace for 3a under a flow of nitrogen with a heating rate of 10 °C min⁻¹.
Figure 3.
Figure 3. Room temperature PXRD patterns of (a) MoSi4 (b) MoSi2 (c) WSi4 and (d) WSi2. Each sample was calcined for 3 h under a flow of oxygen at the temperature indicated.
Figure 4. (a) IR and (b) Raman spectra of MoSi4 and MoSi2.
Figure 5. Yield of cyclohexene oxide relative to initial TBHP as a function of time during the epoxidation of cyclohexene with MoSi4 (◆), MoSi2 (■), WSi4 (▲), and WSi2 (×).